

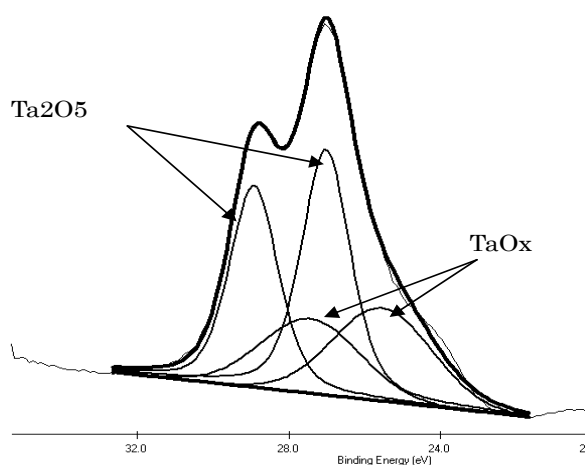
Supporting Information

Enhanced Catalytic Reduction of Oxygen at Tantalum Deposited Platinum Electrode

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| | | |
|-------|--------|--------|
| TaOx | 4f 7/2 | 4f 5/2 |
| | 25.53 | 27.43 |
| Ta2O5 | 27.02 | 28.92 |

Fig. SI-1. Deconvoluted XPS profile of Ta 4f energy level of the Ta/Pt surface. The data was taken from Fig. 3.

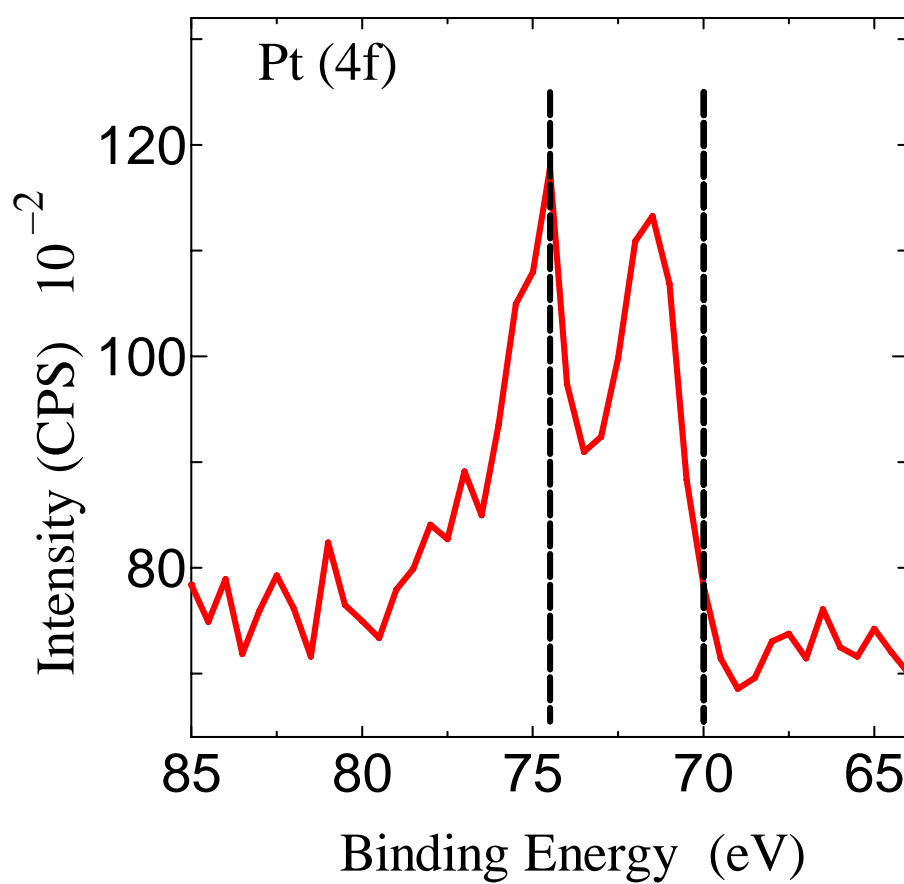


Fig. SI-2. XPS profile of Pt 4f energy level of the underlying Pt surface of the Ta/Pt electrode.

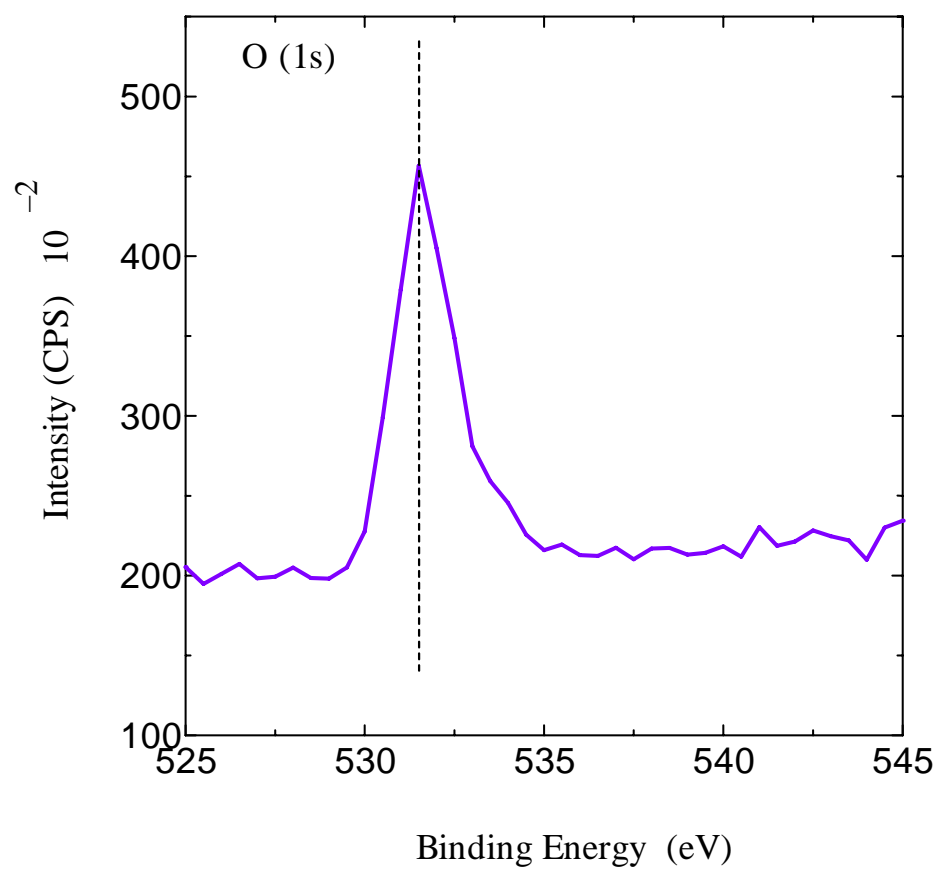


Fig. SI-3. XPS profile of O 1s energy level on the Ta/Pt electrode surface.